

<b>Notice of References Cited</b>	Application/Control No. 09/285,773	Applicant(s)/Patent Under Reexamination MERCALDI ET AL.	
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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
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**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	HOLOUBEK J, Bath for etching chromium silicide layer - is for integrated circuit and is mixture of nitric and hydrofluoric acid, diluted by ethylene glycol, March 14, 1990, 1 page. (English title of CS 8801729 A).
	V	Sapozhniko et al. Determin. of hammer-hardened surface layer thickness - includes treatment with nitric and hydrofluoric acids in glycerine as etching soln. before deformation, 1 page. (English abstract of SU 593110 A).
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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